AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

LISTING OF CLAIMS:

- 1. (Currently Amended) A Process process for deposition of depositing a silver film on a substrate, comprising eonsisting in carrying out a deposition of depositing silver by CVD on said the substrate by chemical vapor deposition of a using a silver precursor solution comprising a silver precursor and a solvent, characterized in that wherein:
 - the silver precursor is a silver carboxylate RCO₂Ag in which R is a linear or branched alkyl radical that has 3 to 7 carbon atoms, used in the form of a solution in an organic liquid;
 - the concentration of the silver precursor in the solution is between 0.01 and 0.6 mol/l;
 - the organic liquid solvent comprises an amine and/or a nitrile, and optionally a solvent compound whose evaporation temperature is less than the decomposition temperature of the silver precursor; and
 - the percentage by volume of the amine and/or the nitrile in the organic liquid solvent is more than 0.1%.
- 2. (Currently Amended) <u>The Process process</u> according to claim 1, wherein the silver precursor is the silver pivalate (CH₃)₃-C-CO₂Ag.

- 3. (Currently Amended) The Process process according to claim 1, wherein the solvent is an organic compound that is liquid at ambient temperature and up to about 200°C under normal pressure conditions.
- 4. (Currently Amended) The Process process according to claim 3, wherein the solvent is selected from among the group consisting of mesitylene, cyclohexane, xylene, toluene and n-octane.
- 5. (Currently Amended) The Process process according to claim 1, wherein the amine is a monoamine that is selected from among the group consisting of n-hexylamine, isobutylamine, disec-butylamine, triethylamine, benzylamine, ethanolamine and diisopropylamine.
- 6. (Currently Amended) The Process process according to claim 1, wherein the amine is a polyamine.
- 7. (Currently Amended) The Process process according to claim 1, wherein the nitrile is selected from among the group consisting of acetonitrile, valeronitrile, benzonitrile and propionitrile.
- 8. (Currently Amended) The Process process according to claim 1, wherein the substrate is formed by a material that is selected from among the group consisting of the superconductive high T_c materials, the ceramics, the thermoresistant polymers, the glasses, MgO, LaAlO₃, Ni, Si, AsGa, InP, SiC and SiGe.

- 9. (Currently Amended) The Process process according to claim 1, wherein the temperature of the substrate to be coated on which silver is to be deposited is between 200 and 450°C.
- 10. (Currently Amended) The Process process according to claim 1, wherein it is implemented silver is deposited on the substrate under in an oxygen atmosphere or under in a hydrogen atmosphere.
- 11. (Currently Amended) The Process process according to claim 1, wherein silver is deposited on the substrate in the presence of a cold plasma is added around the substrate.